

SPECIFICATION AMENDMENTS

Please amend the paragraph 0029 as follows:

0029 FIG. 3 illustrates a block diagram 60 of a laser generator and detection system, in accordance with a preferred embodiment of the present invention. FIG. 3 thus depicts a wafer 68 which may be utilized during the course of a semiconductor fabrication operation, such as, for example, a wafer spin-coating operation. One or more laser light sources are also indicated in FIG. 3. Such laser light sources are laser generator 62 and laser detector 64 65, along with laser generator 82 and laser detector 84. Arrow 72 indicates normal photoresist (PR) dust flow, while arrow 80 indicates abnormal PR dust flow.